# Transistors 1090

## Grinding

| | Steps | PG | FG | FG 2 |
|---|---|---|---|---|
| Surface | Type | SiC Foil #320 | SiC Foil #500 | MD-Largo |
| | Disc speed (rpm) | 300 | 300 | 150 |
| Abrasive | Type | | | DiaPro Allegro/Largo 9 µm |
| | Predosing/dosing | | | 3/6 |
| Lubricant | Type | Water | Water | |
| | Predosing/dosing | | | |
| | Force (N) | 20 | 20 | 30 |
| | Holder direction | >> | >> | >> |
| | Holder speed (rpm) | 150 | 150 | 150 |
| | Time (min) | 1 | 1 | 4 |

## Polishing

| | Steps | DP | DP 2 | OP |
|---|---|---|---|---|
| Surface | Type | MD-Dac | MD-Nap | MD-Chem |
| | Disc speed (rpm) | 150 | 150 | 150 |
| Abrasive | Type | DiaPro Dac 3 µm | DiaPro Nap R 1 µm | OP-U, 0.04 µm |
| | Predosing/dosing | 3/10 | 6/14 | 1/10 |
| Lubricant | Type | | | |
| | Predosing/dosing | | | |
| | Force (N) | 25 | 15 | 10 |
| | Holder direction | >> | >> | >< |
| | Holder speed (rpm) | 150 | 150 | 150 |
| | Time (min) | 3 | 1 | 1 |

## Method comments

The method is developed to fit a standard equipment configuration with 30 mm specimen on 300mm disc. Dosing levels are valid for following equipment: Tegramin, AbraPol and LaboPol

For advice on how to adjust the method to fit your equipment, please take a look at Preparation Parameters.

The preparation time for the plane grinding (PG) step depends very much on the condition of the samples and if they are prepared as single specimens or clamped in a specimen holder. Please check the samples after the first step and repeat it if necessary.

**Take a look at Preparation Parameters**